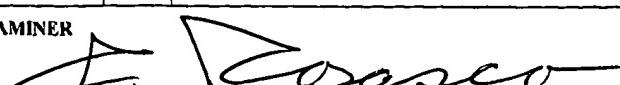


**EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>		Docket Number (Optional) CS02-096	Application Number
		Applicant(s) Lin et al.	
		Filing Date	Group Art Unit
*EXAMINER INITIAL 	OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>		
	<p>Gerold, et al., Multiple Pitch Transmission and Phase Analysis of Six Types of Strong Phase-Shifting Masks, This material was presented at SPIE's 26th Annual International Symposium on Microlithography as presentation number 4346-72 , found on website: <a href="http://www.advlitho.com/content/Papers/4346-72paper.pdf">http://www.advlitho.com/content/Papers/4346-72paper.pdf</a> May 8, 2003. This reference discusses alternating phase shift masks</p> <p>Armen Kroyan and Hua-yu Liu, Effects of altPSM Design on Image Imbalance for 65 nm, Semiconductor International, 2/1/2003 <a href="http://www.e-insite.net/semiconductor/index.asp?layout=article&amp;articleId=CA273367&amp;spacedesc=webex">http://www.e-insite.net/semiconductor/index.asp?layout=article&amp;articleId=CA273367&amp;spacedesc=webex</a>)</p>		
EXAMINER 	DATE CONSIDERED		7-6-05
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